

FEB 13 2004
OFFICIALAttorney Docket No. UMC-98-279 CON
Client Matter No. 81848.0016.001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No. 09/546,174 Application of: LIU, Chih-Chien <i>et al</i> Filed: April 11, 2000 Art Unit: 1711 Examiner: SERGENT, R.A. Attorney Docket No. UMC-98-279 CON For: HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS	Confirmation No.: 4793 Customer No.: 25235
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AMENDMENT AND RESPONSE TO THE OFFICE ACTION
MAILED DECEMBER 23, 2003Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

An Office Action was mailed in the above case December 23, 2003.

Please reconsider the case in light of the amendment and remarks that follow.

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 9 of this paper.

PAGE 3/10 * RCVD AT 23/2004 1:42:34 PM [Eastern Standard Time] * SVR:USPTO-EFXRF-10 * DNS:3723084 * CSD: * DURATION [mm:ss]:04:38

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